

FIG. 1A
PRIOR ART

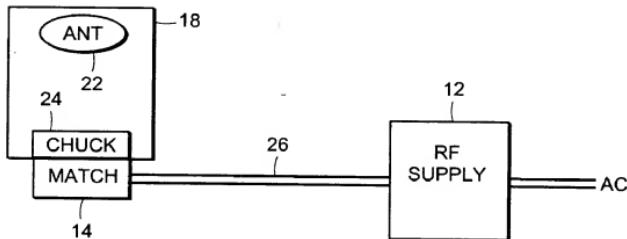


FIG. 1B
PRIOR ART

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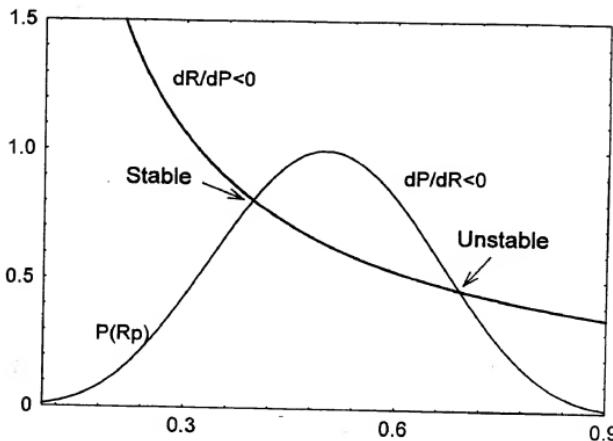


FIG. 2

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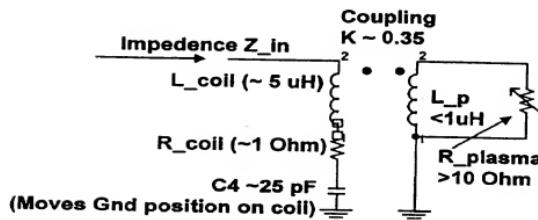


FIG. 3A

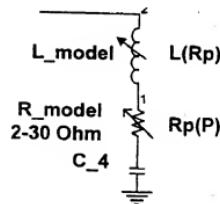


FIG. 3B

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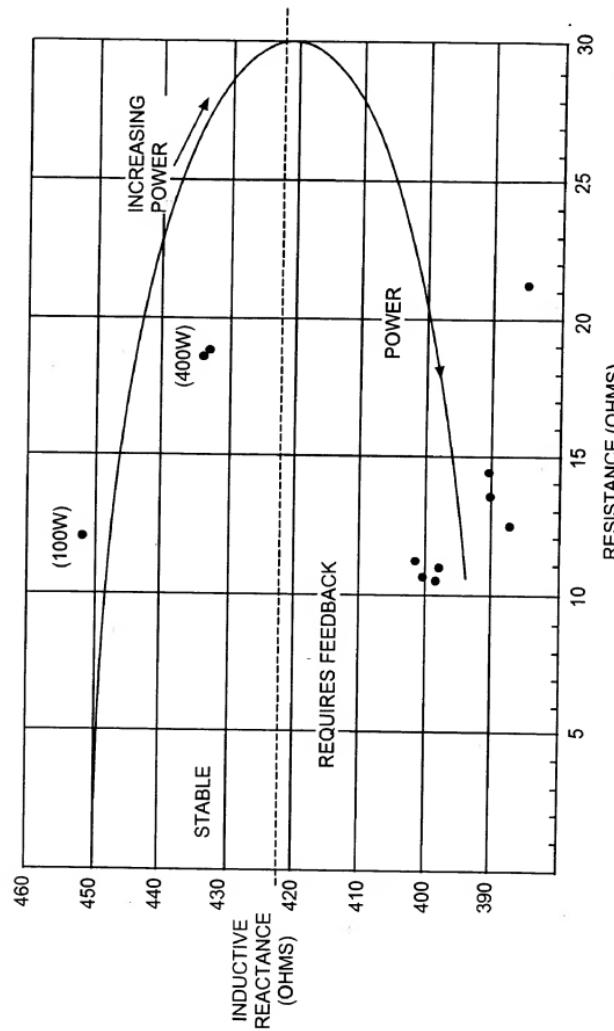


FIG. 4

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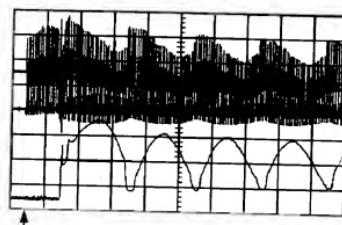


FIG. 5

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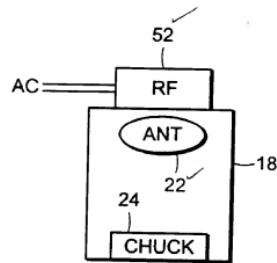


FIG. 6A

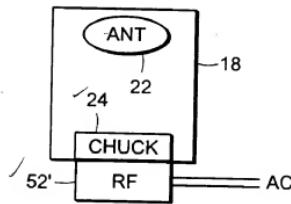
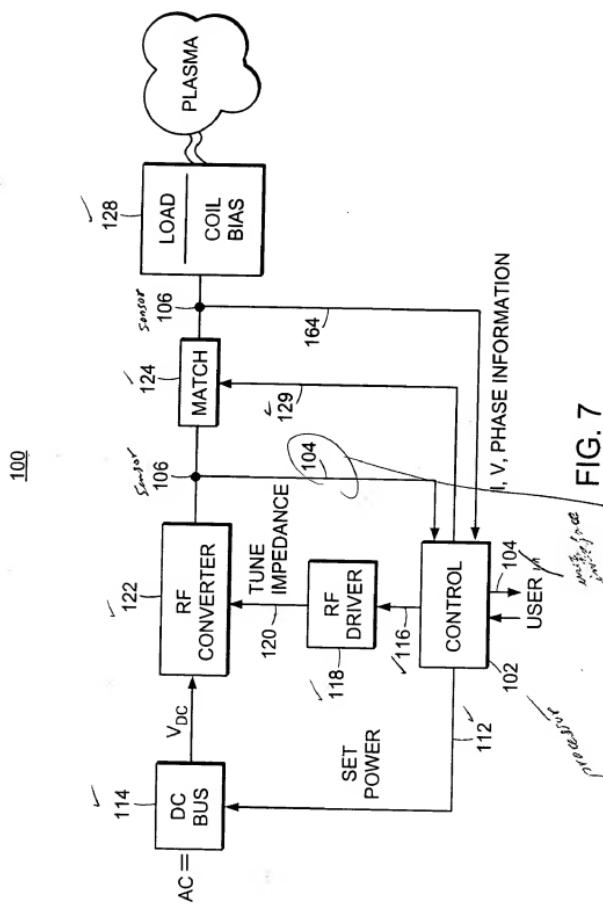


FIG. 6B

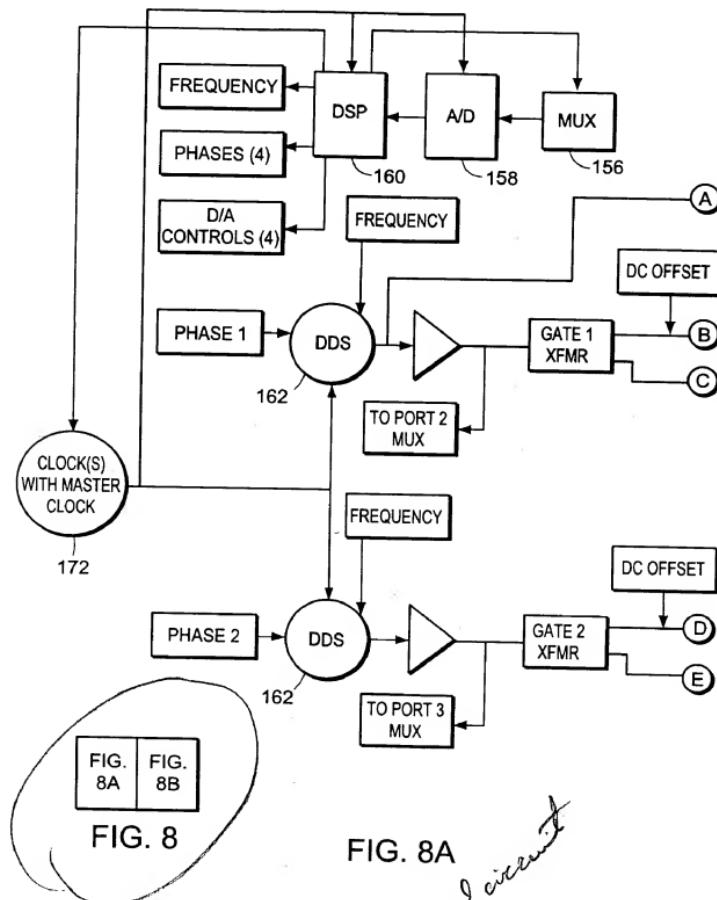
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MUX = MULTIPLEXER
XFMR = TRANSFORMER

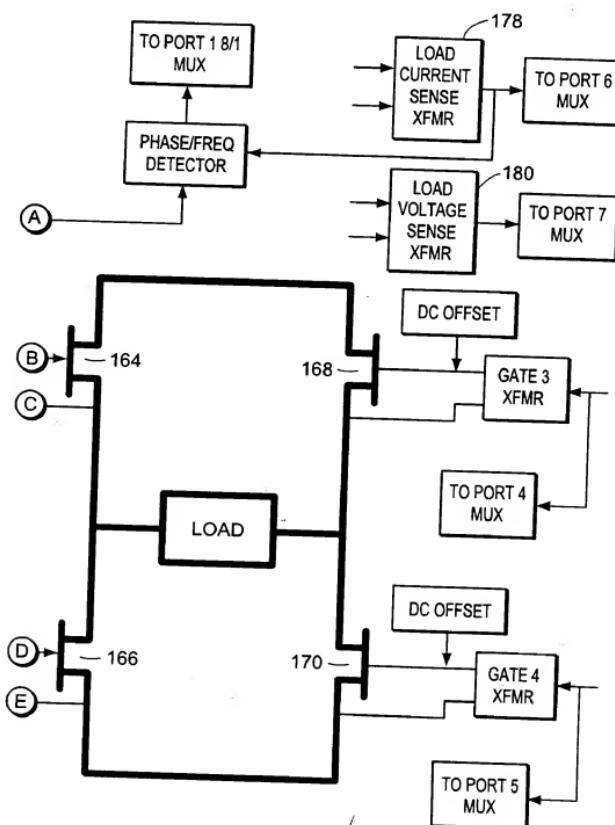


FIG. 8B

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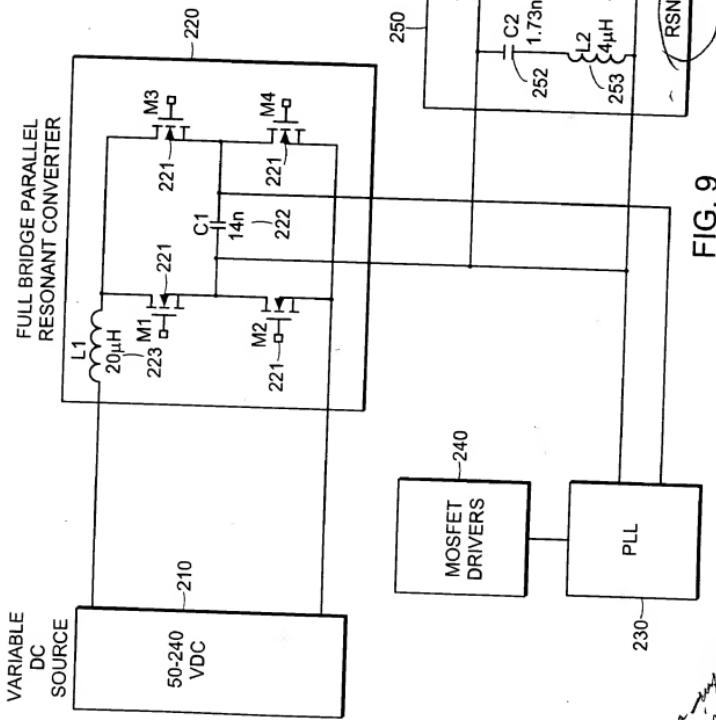
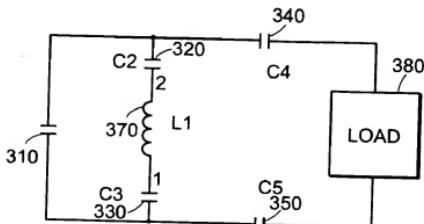


FIG. 9

Normal supply system
including
Resonance stabilizing
networks

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*resonance
at 0.122107*

FIG. 10

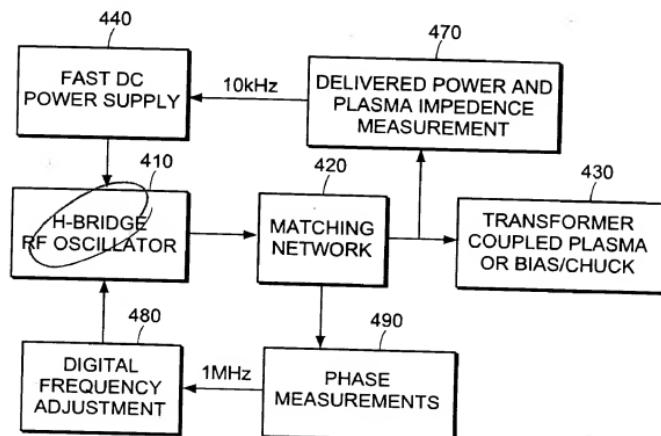


FIG. 11

*RF plasma generator
including
DC power supply
controlled with two loops*

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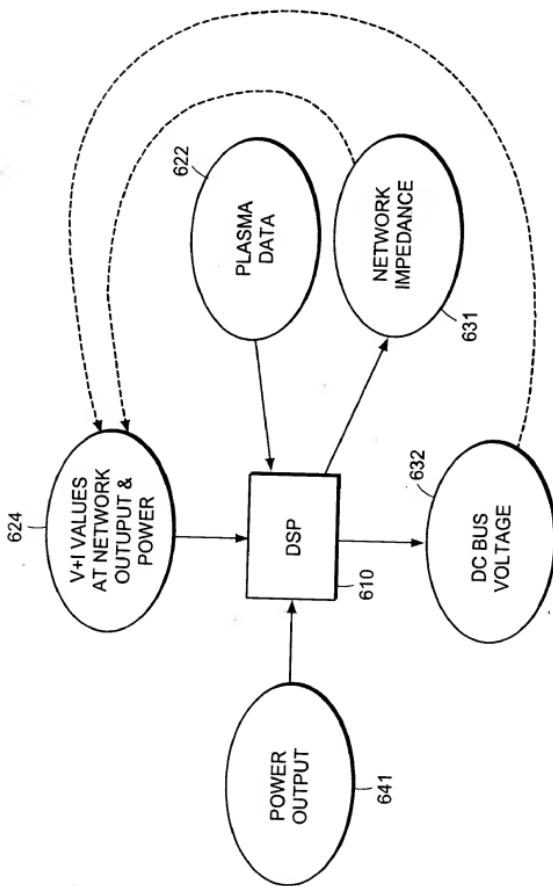


FIG. 12

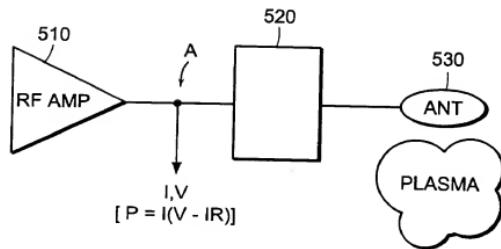


FIG. 13A

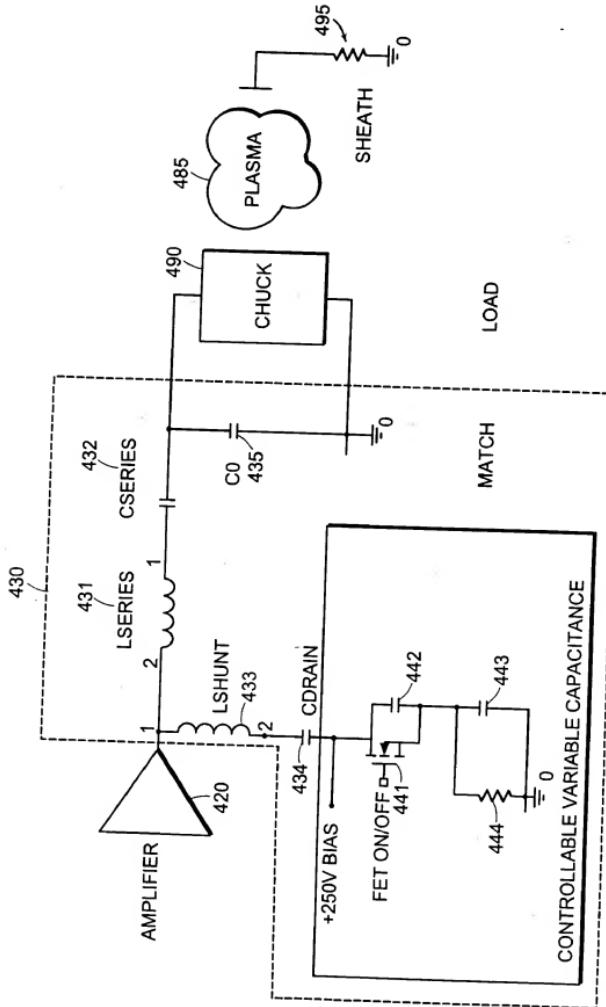


FIG. 13B

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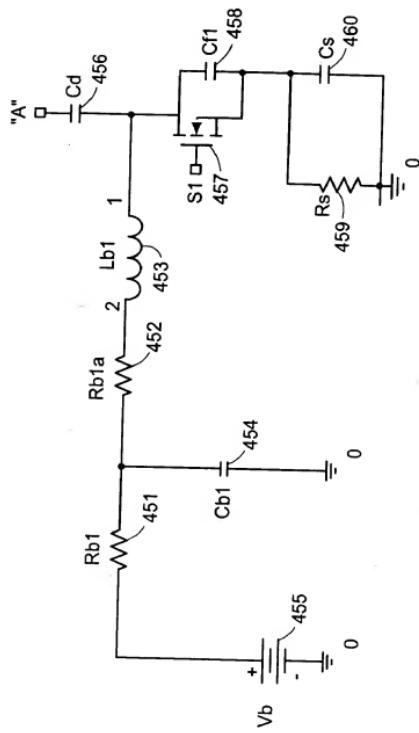


FIG. 14

*smooth matching
network*

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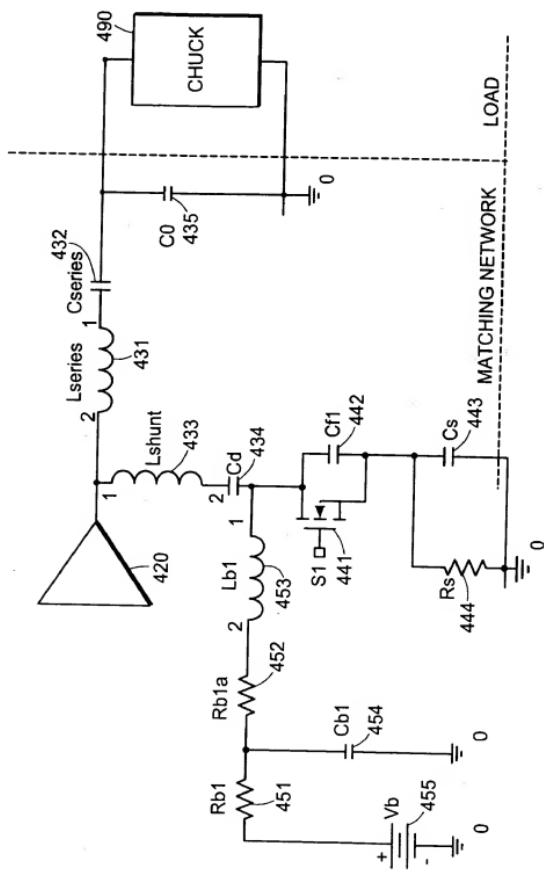


FIG. 15

plasma processing system
including system
matching network

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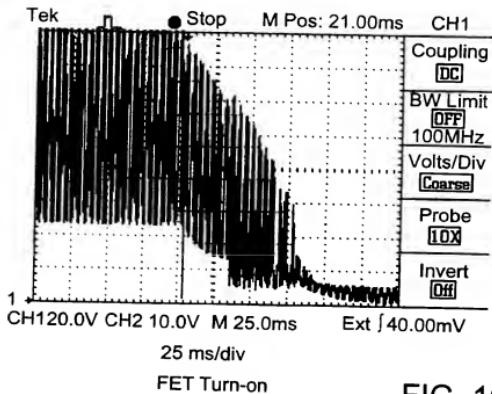


FIG. 16A

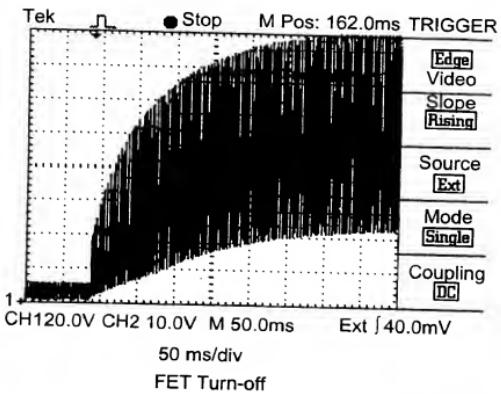


FIG. 16B

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200000-200000

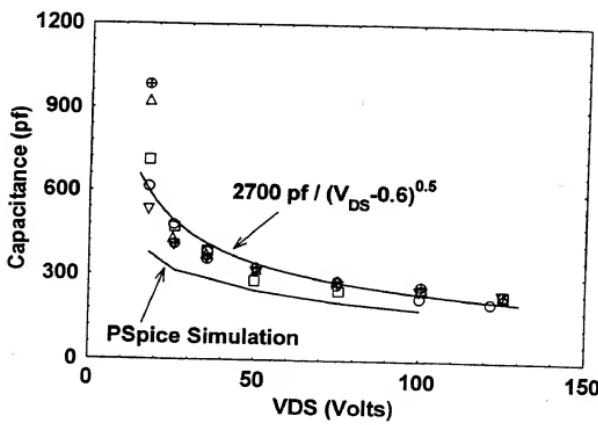


FIG. 17

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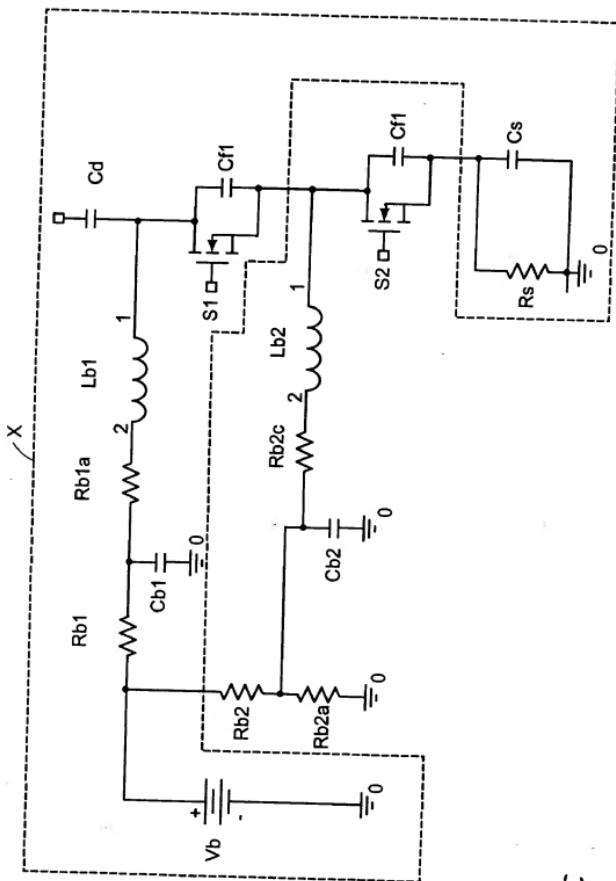


FIG. 18

including
multiple /
smooth match sections

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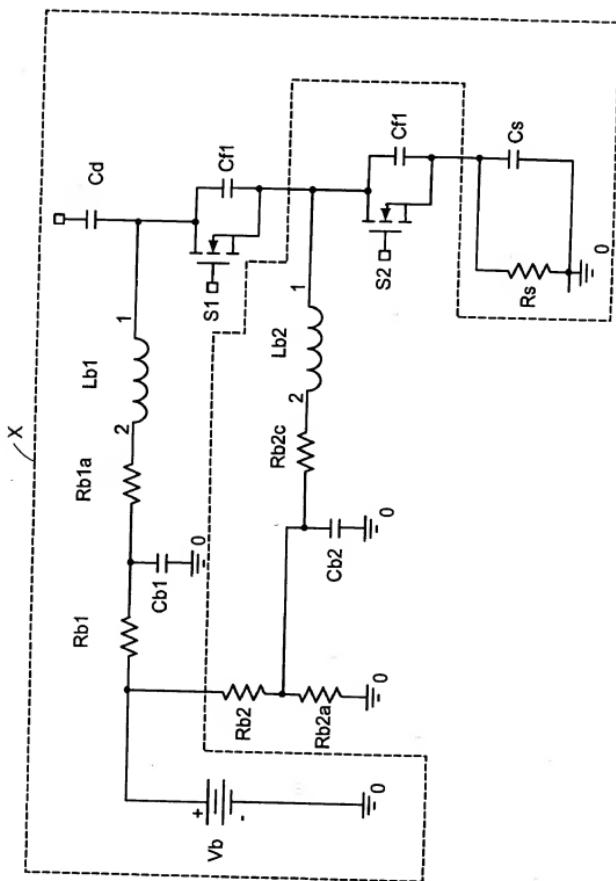


FIG. 18